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APPLICATION NO. FILING DATE		FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/628,898	07/28/2003	Jung-Chih Kuo	10112591	7430	
34283	7590 07/13/2004		EXAMINER		
QUINTERO LAW OFFICE			NGUYEN, HUNG		
1617 BROADWAY, 3RD FLOOR SANTA MONICA, CA 90404			ART UNIT	PAPER NUMBER	
	,		2851		
			DATE MAILED: 07/13/2004	4	

Please find below and/or attached an Office communication concerning this application or proceeding.

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Office Action Summary		Application	No.	Applicant(s)					
		10/628,898	<b>;</b>	KUO, JUNG-CHIH	l				
		Examiner		Art Unit					
		Hung Henry		2851					
The MAILING DATE of this communication appears on the c ver sh et with the correspondence address Period for Reply									
THE - Exte after - If the - If NC - Failu Any	ORTENED STATUTORY PERIOD FO MAILING DATE OF THIS COMMUNIO nsions of time may be available under the provisions of SIX (6) MONTHS from the mailing date of this commu- e period for reply specified above is less than thirty (30 period for reply is specified above, the maximum state re to reply within the set or extended period for reply reply received by the Office later than three months af- ed patent term adjustment. See 37 CFR 1.704(b).	CATION. of 37 CFR 1.13 unication. ) days, a reply utory period w vill, by statute,	36(a). In no even y within the statut vill apply and will , cause the applic	t, however, may a reply be tir ory minimum of thirty (30) day expire SIX (6) MONTHS from ation to become ABANDONE	mely filed ys will be considered timely the mailing date of this oc ED (35 U.S.C. § 133).				
Status									
1) 又	Responsive to communication(s) filed	d on <i>28 Ju</i>	ılv 2003.						
2a)□		·							
3)□									
,—	closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.								
Disp sit	ion of Claims	•							
5)□ 6)⊠ 7)⊠	4)  Claim(s) 1-20 is/are pending in the application.  4a) Of the above claim(s) is/are withdrawn from consideration.  5)  Claim(s) is/are allowed.  6)  Claim(s) 1,2,11 and 12 is/are rejected.  7)  Claim(s) 3-10 and 13-20 is/are objected to.  8)  Claim(s) are subject to restriction and/or election requirement.								
Applicat	on Papers								
10)⊠	The specification is objected to by the The drawing(s) filed on <u>28 July 2003</u> i Applicant may not request that any object Replacement drawing sheet(s) including The oath or declaration is objected to	s/are: a)[ tion to the o the correct	☑ accepted drawing(s) be ion is required	held in abeyance. Se	e 37 CFR 1.85(a). ejected to. See 37 CF	` '			
Priority ι	ınder 35 U.S.C. § 119								
<ul> <li>12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).</li> <li>a) All b) Some * c) None of:</li> <li>1. Certified copies of the priority documents have been received.</li> <li>2. Certified copies of the priority documents have been received in Application No</li> <li>3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).</li> <li>* See the attached detailed Office action for a list of the certified copies not received.</li> </ul>									
2) Notice 3) Information	t(s) se of References Cited (PTO-892) se of Draftsperson's Patent Drawing Review (PT mation Disclosure Statement(s) (PTO-1449 or F r No(s)/Mail Date <u>7/03</u> .			4) Interview Summary Paper No(s)/Mail D 5) Notice of Informal F 6) Other:	ate	)-152)			

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#### **DETAILED ACTION**

### Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- (e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371(c) of this title before the invention thereof by the applicant for patent.

The changes made to 35 U.S.C. 102(e) by the American Inventors Protection Act of 1999 (AIPA) and the Intellectual Property and High Technology Technical Amendments Act of 2002 do not apply when the reference is a U.S. patent resulting directly or indirectly from an international application filed before November 29, 2000. Therefore, the prior art date of the reference is determined under 35 U.S.C. 102(e) prior to the amendment by the AIPA (pre-AIPA 35 U.S.C. 102(e)).

2. Claims 1-2 and 11-12 are rejected under 35 U.S.C. 102(b) as being anticipated by Ausschnitt et al (U.S.Pat. 5,965,309).

With respect to claims 1 and 11, Ausschitt et al (figures 19-20) discloses an exposure system and corresponding method comprising all basic features of the instant claims such as: a

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compensation unit (see block 358; see col.17, lines 7-22) to receive at least one adjustment value of a corresponding overlay parameter according to the adjustment value and an adjustment formula (see block 356) corresponding to the equipment parameter and an exposure apparatus to perform overlay and exposure processes on a wafer in accordance with the compensated overlay parameter.

As to claims 2 and 13, Ausschitt discloses the compensation unit calculates a compensation value according to the adjustment value and the adjustment formula, and compensates the overlay parameter using the compensation value (see col.5, lines 40 through col.6, line 33).

3. Claims 1-2 and 11-12 are rejected under 35 U.S.C. 102(e) as being anticipated by Jun et al (U.S.Pat. 6,700,648).

With respect to claims 1 and 11, Jun et al (figure 1) discloses an exposure system and corresponding method comprising all basic features of the instant claims such as: a compensation unit (30) to receive at least one adjustment value of a corresponding overlay parameter according to the adjustment value and an adjustment formula (for example, please see col.4, lines 10-15; col.8, lines 30-60) corresponding to the equipment parameter and an exposure apparatus (10) to perform overlay and exposure processes on a wafer in accordance with the compensated overlay parameter.

As to claims 2 and 13, Ausschitt discloses the compensation unit calculates a compensation value according to the adjustment value and the adjustment formula, and compensates the overlay parameter using the compensation value (see abstract and claim 1).

4. Claims 1-2, 11-12 are rejected under 35 U.S.C. 102(e) as being anticipated by Matsumoto et al (US 2002/0111038).

With respect to claims 1 and 11, Matsumoto et al (figures 1-2) discloses an exposure system and corresponding method comprising all basic features of the instant claims such as: a compensation unit (31) to receive at least one adjustment value of a corresponding overlay parameter according to the adjustment value and an adjustment formula (see section [0049]) corresponding to the equipment parameter and an exposure apparatus (21-22) to perform overlay and exposure processes on a wafer in accordance with the compensated overlay parameter.

As to claims 2 and 13, Matsumoto et al discloses the compensation unit calculates a compensation value according to the adjustment value and the adjustment formula, and compensates the overlay parameter using the compensation value (see section [0055]).

### Allowable Subject Matter

- 5. Claims 3-10, 13-20 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.
- 6. The following is a statement of reasons for the indication of allowable subject matter:

  Claims 3-10 and 13-20 have been found allowable since while the prior art of record teaches an exposure apparatus having a compensation unit, and an exposure device but does not specifically teach computing the equipment parameter based on the formula, and satisfying conditions as recited in the instant claims.

## Prior Art Made of Record

7. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Ogata (U.S.Pat. 6,221,787) and Bode et al (U.S.Pat. 6,368,883) disclose exposure systems, each of which comprises substantially all elements as recited in the instant claims of the present application.

8. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Hung Henry V Nguyen whose telephone number is 571-272-2124. The examiner can normally be reached on Monday-Friday (First Friday off).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Russ Adams can be reached on 571-272-2112. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Hung Henry V Nguyen Primary Examiner Art Unit 2851

hvn 7/7/04